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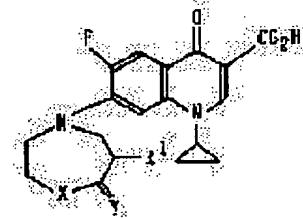
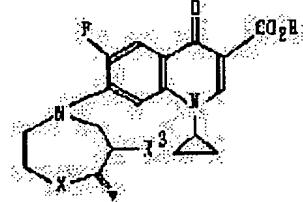
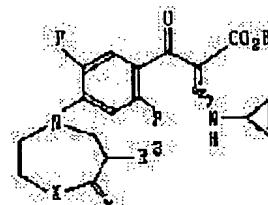
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(54) PRODUCTION OF QUINOLONE CARBOXYLIC ACID DERIVATIVE AND IT INTERMEDIATE

(57)Abstract:

PURPOSE: To obtain the subject compound useful as an antimicrobial agent in high yield and high purity by cyclizing an acrylic acid derivative in the presence of a basic catalyst and then hydrolyzing the cyclized compound.

CONSTITUTION: A compound of formula I [R is lower alkyl, aralkyl or ester residue; R3 is H or N-R4R5; R4 and R5 are H, lower alkyl or protecting group of amino; X is methylene, O, S or SO₂, NR₂, etc.; R₂ is H or lower alkyl; Y is O or H₂] is cyclized in the presence of a basic catalyst (e.g. NaOH) in a solvent (e.g. acetonitrile) at 0° C to boiling point of the solvent to provide a quinolone carboxylic acid ester of formula II. Then, the compound of formula II is hydrolyzed and as necessary, a protecting group of the amino group of R₃ is removed to provide the objective compound of formula III (R₁ is H or amino which may be substituted with alkyl group).



LEGAL STATUS

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